

Figure 1. High-resolution XRD  $\omega$ -2 $\theta$  scans of InAlAs PIN diodes containing As<sub>2</sub> and As<sub>4</sub>.



Figure 3. Carrier concentration versus depletion depth for the two InAlAs PIN diodes, showing a reduction in UID concentration with the use of As<sub>4</sub>.



Figure 2. Light (solid lines) and dark (dashed lines) IV measurements for InAlAs PIN diodes containing As<sub>2</sub> and As<sub>4</sub>.



Figure 4. Dark field microscopy images of both PIN diodes, showing comparable defect densities of  $\sim$ 2000 defects/cm<sup>2</sup>.